

What is claimed is:

1. An aligner comprising a base for resting a to-be-exposed substrate thereon and a sucking unit for sucking the to-be-exposed substrate on said base, said sucking unit being capable of sucking the to-be-exposed substrate only at a part thereof.

2. An aligner according to claim 1, wherein said aligner is capable of partly exposing the to-be-exposed substrate to light, said sucking unit being capable of sucking the to-be-exposed substrate only at a part for exposure to light.

3. An aligner comprising:
a base for resting a to-be-exposed substrate thereon;
a photomask having a predetermined pattern for projection onto the to-be-exposed substrate on said base and to be contacted with or proximate to the to-be-exposed substrate;

a moving unit for moving at least one of said photomask and said base to change and set a relative positional relationship of the both;

a light source unit for radiating light for projection of the pattern of said photomask onto the to-be-exposed substrate on said base;

an aligning unit for aligning the photomask and the to-be-exposed substrate in an arbitrary area of the to-be-exposed substrate;

a sucking unit for sucking the to-be-exposed substrate at each area corresponding to the arbitrary area on said base; and

a control unit for controlling said moving unit, said aligning unit and

said light source unit such that the to-be-exposed substrate is sucked at each of the areas on said base and, after alignment, exposed to light.

4. An aligner according to claim 3, wherein the photomask is positioned
5 vertically above the to-be-exposed substrate.

5. An aligner according to claim 3, wherein the photomask and the
to-be-exposed substrate are positioned with a spacing nearly in a horizontal
direction.

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6. An aligner comprising:

a base for resting a to-be-exposed substrate thereon;

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a photomask having a predetermined pattern for projection onto the
to-be-exposed substrate on said base and to be contacted with the to-be-exposed
substrate;

a moving unit for moving at least one of said photomask and said base
to change and set a relative positional relationship of the both;

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a light source unit for radiating light for projection of the pattern of the
photomask contacting the to-be-exposed substrate onto the to-be-exposed
substrate;

an aligning unit for aligning such that the photomask is to contact an
arbitrary area of the to-be-exposed substrate;

a sucking unit for sucking only the area of the to-be-exposed substrate
to be contacted by the photomask onto said base;

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a control unit for controlling said moving unit, said aligning unit and

said light source unit such that the to-be-exposed substrate at each of the area is sucked on said base and, after alignment, exposed to light.

7. An aligner according to claim 6, wherein the photomask is positioned
5 vertically above the to-be-exposed substrate.

8. An aligner according to claim 6, wherein the photomask and the to-be-exposed substrate are positioned with a spacing nearly in a horizontal direction.

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